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APPLICATION NO.	FILING DATE		FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/726,264		12/02/2003	Alessio M. D'arrigo Guiseppe	61181-7USPX	3369	
23932	7590	09/06/2005		EXAMINER		
JENKENS (•	AHMED, SHAMIM			
1445 ROSS A SUITE 3200				ART UNIT	PAPER NUMBER	
DALLAS, T	X 75202	2	1765	<u> </u>		
				DATE MAILED: 09/06/200	5	

Please find below and/or attached an Office communication concerning this application or proceeding.

U.S. Patent and Trademark Office PTOL-326 (Rev. 7-05)	Office Ac	tion Summary	Part of Pap	er No./Mail Date	20050830				
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Re 3) Information Disclosure Statement(s) (PTO-1 Paper No(s)/Mail Date U.S. Petent and Trademark Office		5) <u>P</u>	nterview Summary (PTO-41 aper No(s)/Mail Date otice of Informal Patent Ap ther:	_•	52)				
* See the attached detailed Office action for a list of the certified copies not received.									
application from the International Bureau (PCT Rule 17.2(a)).									
3. Copies of the certified copies of the priority documents have been received in this National Stage									
I	2. Certified copies of the priority documents have been received in Application No								
a)⊠ All b)⊡ Some c)⊡ None of: 1.⊠ Certified copies of the priority documents have been received.									
12)⊠ Acknowledgment is made of a a)⊠ All b)□ Some * c)□ None		priority under 35 l	J.S.C. § 119(a)-(d) or	(f) .					
Priority under 35 U.S.C. § 119									
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.									
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).									
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).									
10)⊠ The drawing(s) filed on <u>02 December 2003</u> is/are: a)⊠ accepted or b)□ objected to by the Examiner.									
9) The specification is objected to	by the Examine	r.							
Application Papers									
8) Claim(s) are subject to									
7)☐ Claim(s) is/are objected to.									
5) Claim(s) is/are allowed. 6) Claim(s) <u>1-13 and 19-35</u> is/are rejected.									
4a) Of the above claim(s) 14-18 is/are withdrawn from consideration.									
4) Claim(s) <u>1-35</u> is/are pending in the application.									
Disposition of Claims		·							
closed in accordance with the	practice under E	x parte Quayle, 19	935 C.D. 11, 453 O.G.	213.					
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.								
2a)☐ This action is FINAL .		action is non-final							
1) Responsive to communication	(s) filed on <u>02 D</u>	<u>ecember 2003</u> .							
Status					,				
WHICHEVER IS LONGER, FROM T - Extensions of time may be available under the pr after SIX (6) MONTHS from the mailing date of the f NO period for reply is specified above, the max - Failure to reply within the set or extended period Any reply received by the Office later than three r earned patent term adjustment. See 37 CFR 1.7	THE MAILING DA rovisions of 37 CFR 1.13 his communication. dimum statutory period we for reply will, by statute, months after the mailing	ATE OF THIS CON 36(a). In no event, howev vill apply and will expire SI cause the application to I	MMUNICATION. er, may a reply be timely filed X (6) MONTHS from the mailin become ABANDONED (35 U.S	g date of this comm .C. § 133).					
Period for Reply A SHORTENED STATUTORY PERI	IOD EOR REDI V	/ IS SET TO EYD	PE 2 MONTH(S) OP	THIRTY (30)	DAVS				
The MAILING DATE of this col	mmunication app			ondence addre	9ss				
	•	Examiner Shamim Ahmed	1765	III.					
Office Action Summa	rv	10/726,264		D'ARRIGO GUISEPPE ET AL.					
				, ,					
		Application No.	Applie	ant(s)					

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DETAILED ACTION

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Election/Restrictions

- 1. Restriction to one of the following inventions is required under 35 U.S.C. 121:
 - I. Claims 1-13 and 19-35, drawn to a process, classified in class 216, subclass 2.
- II. Claims 14-18, drawn to a product, classified in class 257, subclass 536.The inventions are distinct, each from the other because of the following reasons:
- 2. Inventions I and II are related as process of making and product made. The inventions are distinct if either or both of the following can be shown: (1) that the process as claimed can be used to make other and materially different product or (2) that the product as claimed can be made by another and materially different process (MPEP § 806.05(f)). In the instant case the product as claimed can be made by another and materially different process such as by drilling or laser ablation or punching.
- 3. Because these inventions are distinct for the reasons given above and have acquired a separate status in the art as shown by their different classification, restriction for examination purposes as indicated is proper.
- 4. During a telephone conversation with Andre M. Szuwalski on 8/11/05 a provisional election was made **without** traverse to prosecute the invention of Group I, claims 1-13 and 19-35. Affirmation of this election must be made by applicant in replying to this Office action. Claims 14-18 are withdrawn from further consideration by the examiner, 37 CFR 1.142(b), as being drawn to a non-elected invention.

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5. Applicant is reminded that upon the cancellation of claims to a non-elected invention, the inventorship must be amended in compliance with 37 CFR 1.48(b) if one or more of the currently named inventors is no longer an inventor of at least one claim remaining in the application. Any amendment of inventorship must be accompanied by a request under 37 CFR 1.48(b) and by the fee required under 37 CFR 1.17(i).

Claim Objections

6. Claims 22 and 32 are objected to because of the following informalities: Both the claims recite the term "KHOH" should have been "KOH". Appropriate correction is required.

Claim Rejections - 35 USC § 112

- 7. The following is a quotation of the second paragraph of 35 U.S.C. 112:

 The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.
- 8. Claim 3 is rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.
- 9. Regarding claim 3, the phrase "plasma etching is performed with a TMAH or KOH solution" renders the claim indefinite because it is unclear whether the solution is directed to the plasma etching or the wet anisotropic etching.

Claim Rejections - 35 USC § 102

10. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

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(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

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- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 11. Claims 1, 28-29 and 33-35 are rejected under 35 U.S.C. 102(b) as being anticipated by Yoshino (6,153,488).

Yoshino disclose a process including the steps of forming a monocrystalline silicon layer (63) over a silicon substrate (61) and forming a deep trench (65) through both the silicon layers and then closing the top port opening of the deep trench with polysilicon layer (67) (col.9, lines 16-32 and figures 18-19).

12. Claims 1-5 are rejected under 35 U.S.C. 102(e) as being anticipated by Kudelka et al (6,426,254).

Kudelka et al disclose a process of forming a trench on a monocrystalline silicon substrate by plasma etching through masking layer comprises silicon nitride using a photolithographic process and after forming the trench, the entire trench is widened by wet anisotropic etching process in order to form a deep trench or deep cavity, which resembles the claimed microchannel (col.2, lines 1-10 and col.4, lines 14-33).

Kudelka et al also disclose the entire cavity is nearly buried in the monocrystalline substrate as shown in figure 17.

Kudelka et al also teach that the wet anisotropic etching is performed using ammonium hydroxide or potassium hydroxide (KOH) (col.5, lines 61-col.6, line 2).

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Claim Rejections - 35 USC § 103

13. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

- 14. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).
- 15. Claims 6-13 and 19-32 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kudelka et al (6,426,254) in view of Urakami et al (6,406,982) or Jun et al (6,582,987).

Kudelka et al discusses above in the paragraph 12.

As to claims 6-7, Kudelka et al also teach that depositing or forming doped silicon layer and the concentration of the dopant would have been obvious to optimize as desired by the skilled artisian at the time of claimed invention.

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Kudelka et al fail to teach epitaxial growing operation effective to close an upper part of the microchannel.

However, Urakami et al teach that after forming a trench the trench is covered or enclosed by an epitaxially grown layer of polysilicon in order to efficiently burring the trench (col.16, lines 13-19).

Additionally, Jun et al disclose a process of fabricating microchannel array embedded in silicon substrate, wherein polysilicon layer (103,203) is deposited on top of the opening of the micropores (211) for easily forming microchannels embedded in the silicon substrate (col.5, lines 1-27).

Therefore, it would have been obvious to one of ordinary skilled in the art at the time of claimed invention to combine Urakami et al or Jun et al's teaching into Kudelka et al's process for efficiently forming buried microchannels as taught by Urakami et al or Jun et al.

Conclusion

16. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Erratico et al (US 2001/0049200) disclose a process for forming a buried cavity in a semiconductor wafer.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shamim Ahmed whose telephone number is (571) 272-1457. The examiner can normally be reached on M-Thu (7:00-5:30) Every Friday Off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine G. Norton can be reached on (571) 272-1465. The fax phone

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number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Shamim Ahmed Primary Examiner Art Unit 1765

SA August 31, 2005